

Form PTO-1449 (modified)

Atty. Docket No.  
2000.089400/SFDSerial No.  
09/897,573

List of Patents and Publications for Applicant's

Applicants

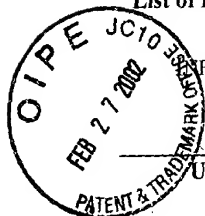
Richard J. Markle, et al.

INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Filing Date:  
July 2, 2001Group:  
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Foreign Patent Documents

Other Art  
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## U.S. Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date of App.
WD	A1	5,880,838	3/9/1999	Marx, et al.	356	351	6/5/1996
WD	A2	5,867,276	2/2/1999	McNeil, et al.	356	445	3/7/1997
WD	A3	5,393,624	2/28/1995	Ushijima	430	30	8/3/1992

## Foreign Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Country	Class	Sub Class	Translation Yes/No

## Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation
WD	C1	Bishop <i>et al.</i> , "Use of Scatterometry for resist process control," <i>SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 1673:441-452, 1992.
WD	C2	Hickman <i>et al.</i> , "Use of diffracted light from latent images to improve lithography control," <i>SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 1464:245-257, 1991.
WD	C3	McNeil <i>et al.</i> , "Scatterometry applied to microelectronics processing - Part 1," <i>Solid State Technology</i> , 37(3):29-56, 1993.
WD	C4	Miller and Mellicamp, "Development of an end-point detection procedure for the post-exposure bake process," <i>Integrated circuit metrology, inspection, and process control LX: 20-22, February, 1995, Santa Clara, California, SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 2439:78-88, 1995.
WD	C5	Milner <i>et al.</i> , "Latent image exposure monitor using scatterometry," <i>SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 1673:274-283, 1992.
WD	C6	Prins <i>et al.</i> , "Scatterometric sensor for PEB process control," <i>Metrology, inspection, and process control for microlithography, X: 11-13, March, 1996, Santa Clara, California, SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 2725:710-719, 1996.

EXAMINER:

Willie Davis

DATE CONSIDERED:

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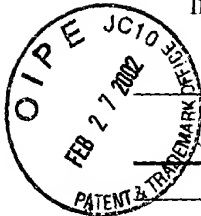
U.S. Patent Documents

See Page 1

Foreign Patent Documents

Other Art

See Page 1-2



## Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation
WD	27 C8	Raymond <i>et al.</i> , "Multiparameter process metrology using scatterometry," In: <i>Optical characterization techniques for high-performance microelectronic device manufacturing II</i> , SPIE - The International Society for Optical Engineering, 2638:84-93, Austin, Texas, October 25-26, 1995.
WD	28 C7	Raymond <i>et al.</i> , "Scatterometric sensor for lithography," In: <i>Manufacturing process control for microelectronic devices and circuits</i> , SPIE - The International Society for Optical Engineering, 2336:37-49, Austin, Texas, October 20-21, 1994.
WD	C9	Sturtevant <i>et al.</i> , "Post-exposure bake as a process-control parameter for chemically-amplified photoresist," <i>Metrology, inspection, and process control for microlithography</i> , VII:2-4, March, 1993, Santa Jose, California, SPIE Integrated Circuit Metrology, Inspection and Process Control, vol. 1926, 1993.
WD	C10	Sturtevant <i>et al.</i> , "Use of scatterometric latent image detector in closed loop feedback control of linewidth," <i>SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 2196:352-359, 1994.

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